

Fig. 1

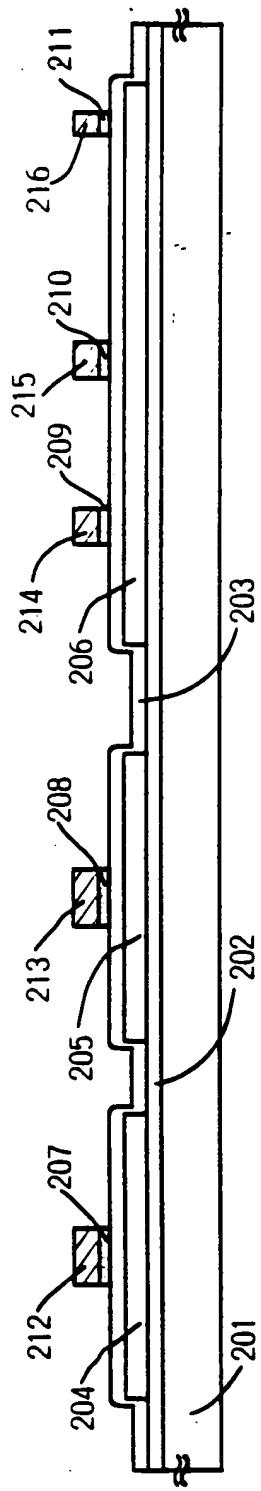


Fig. 2A

↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓

Addition of N-type impurity
(Low concentration)

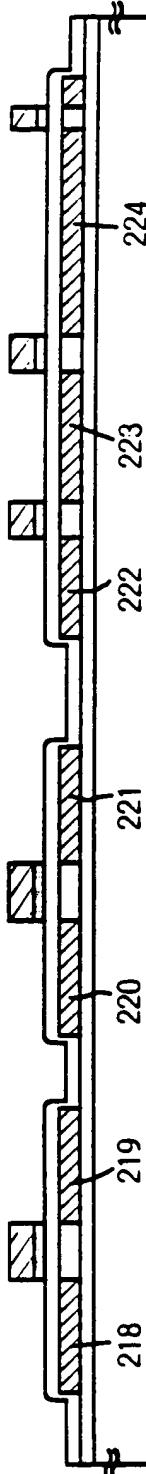


Fig. 2B

↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓

Addition of P-type impurity
(High concentration)

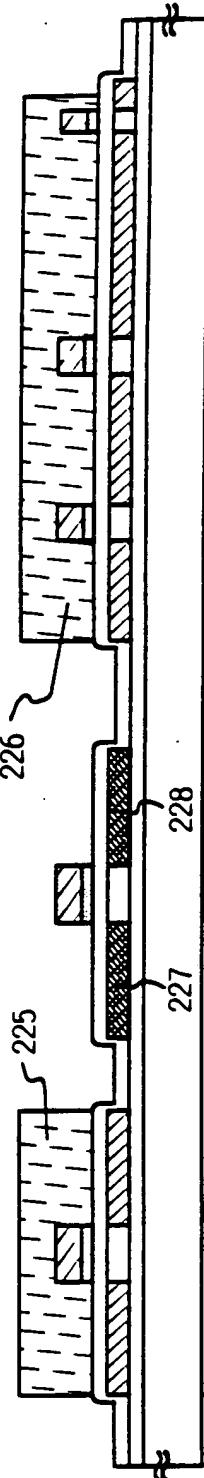


Fig. 2C

Addition of N-type impurity
(High Concentration)

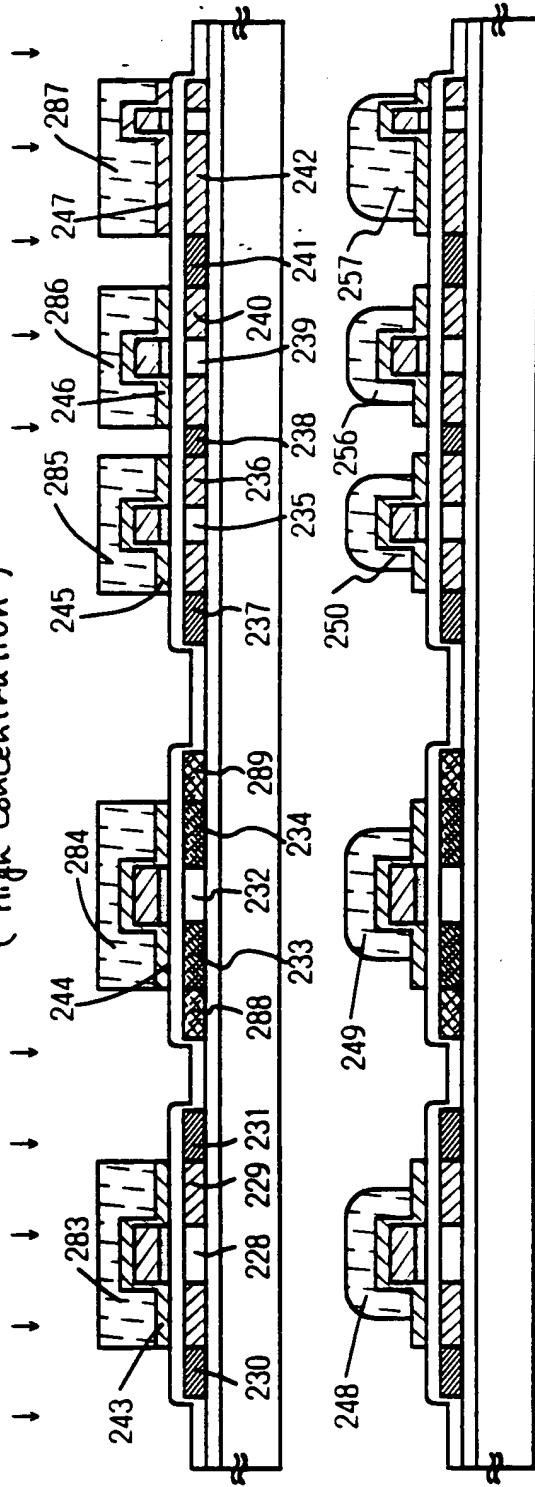
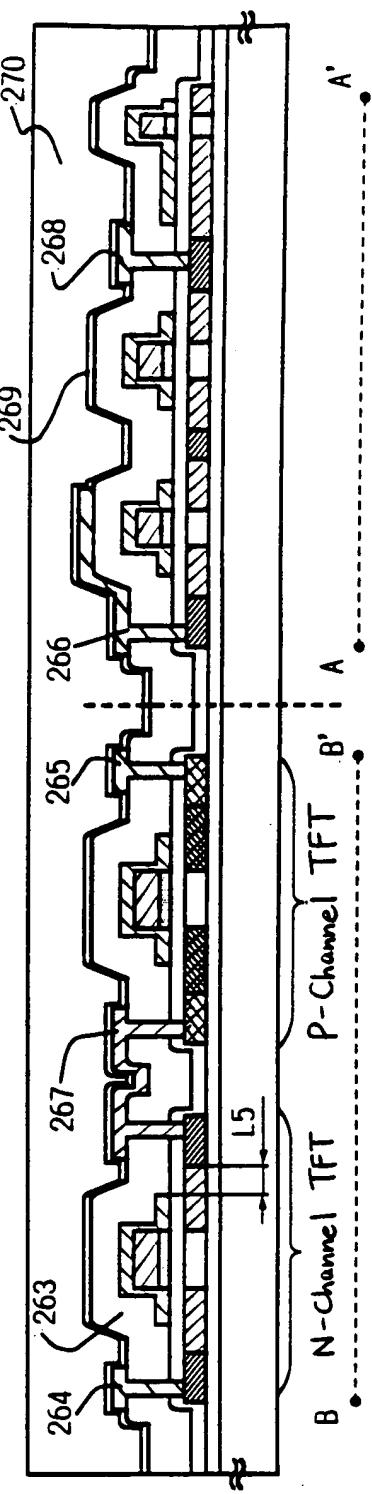


Fig. 3A

Fig. 3B

Fig. 3C



CMOS Circuit

Pixel Matrix Circuit

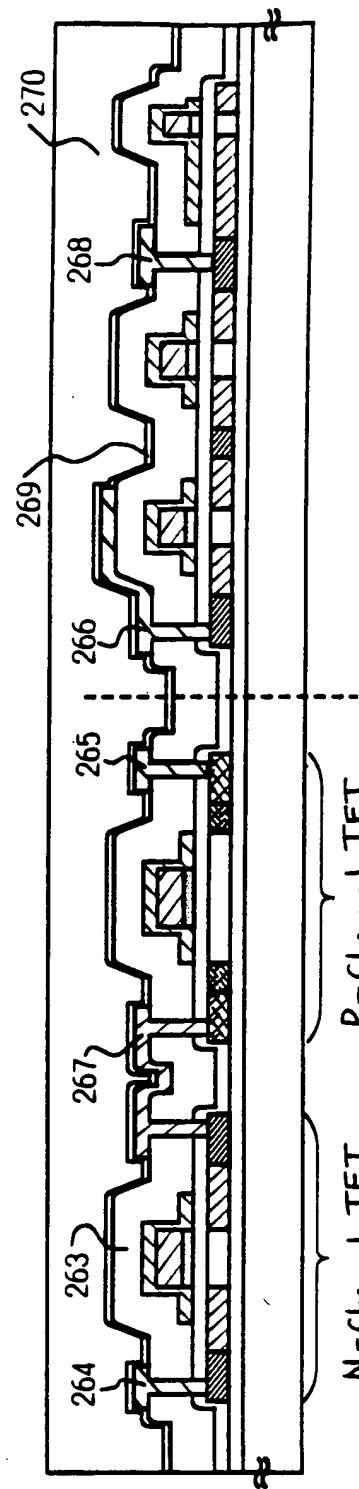


Fig. 4B
Pixel Matrix Circuit
CMOS Circuit
P-Channel TFT

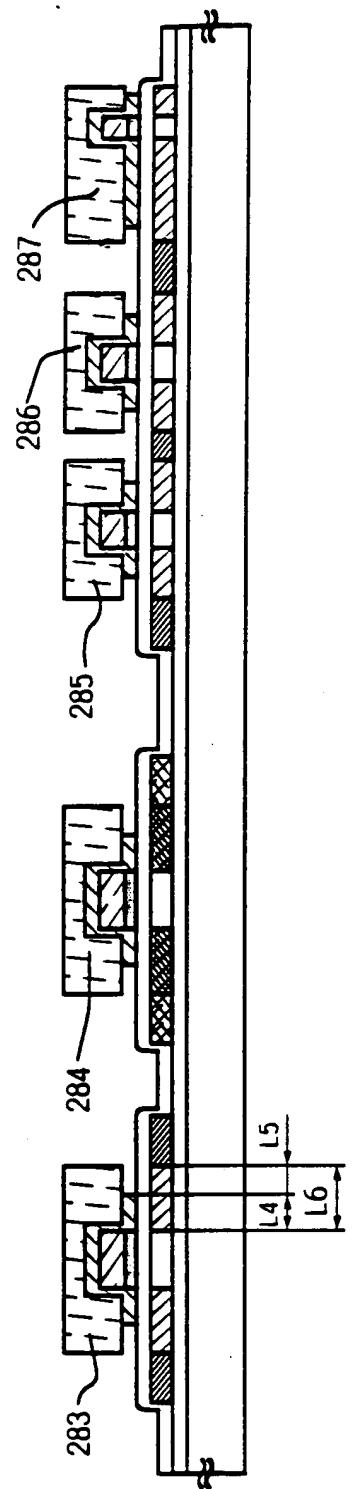


Fig. 4A

CMOS Circuit
Pixel Matrix Circuit

Fig. 5A

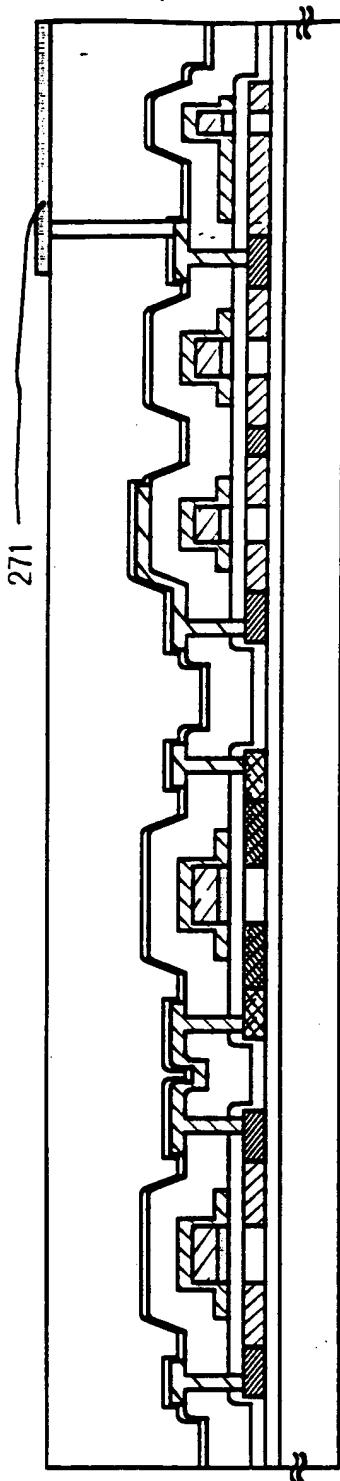
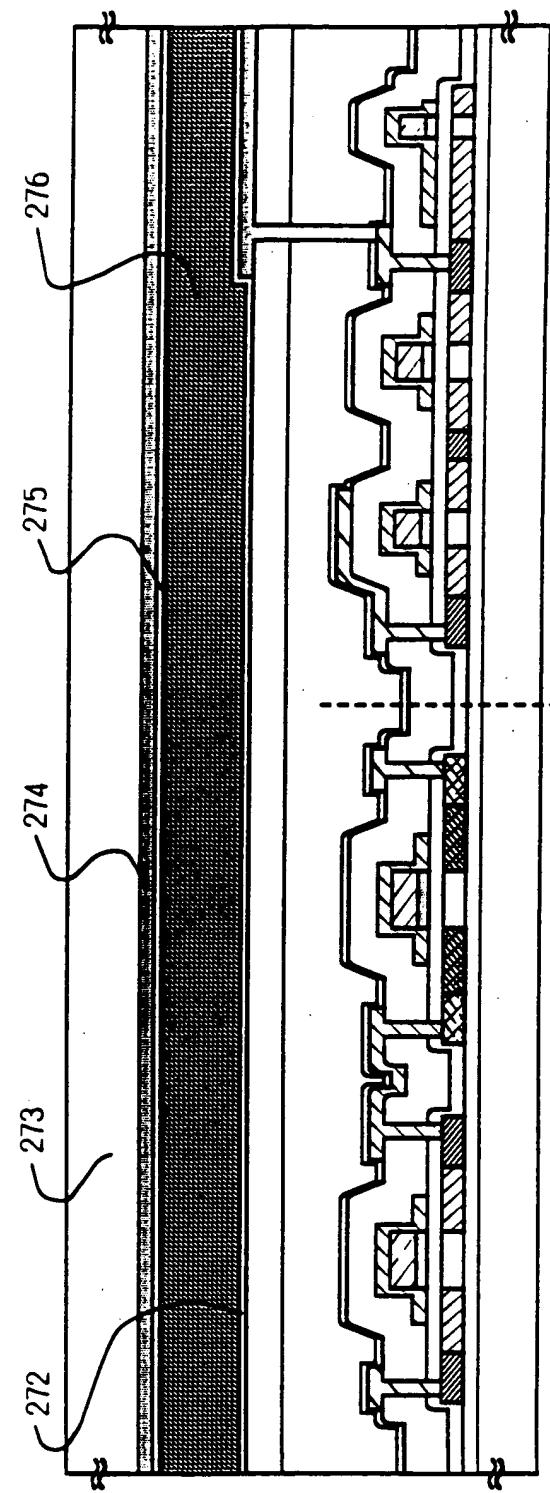


Fig. 5B



Addition of N-type impurity

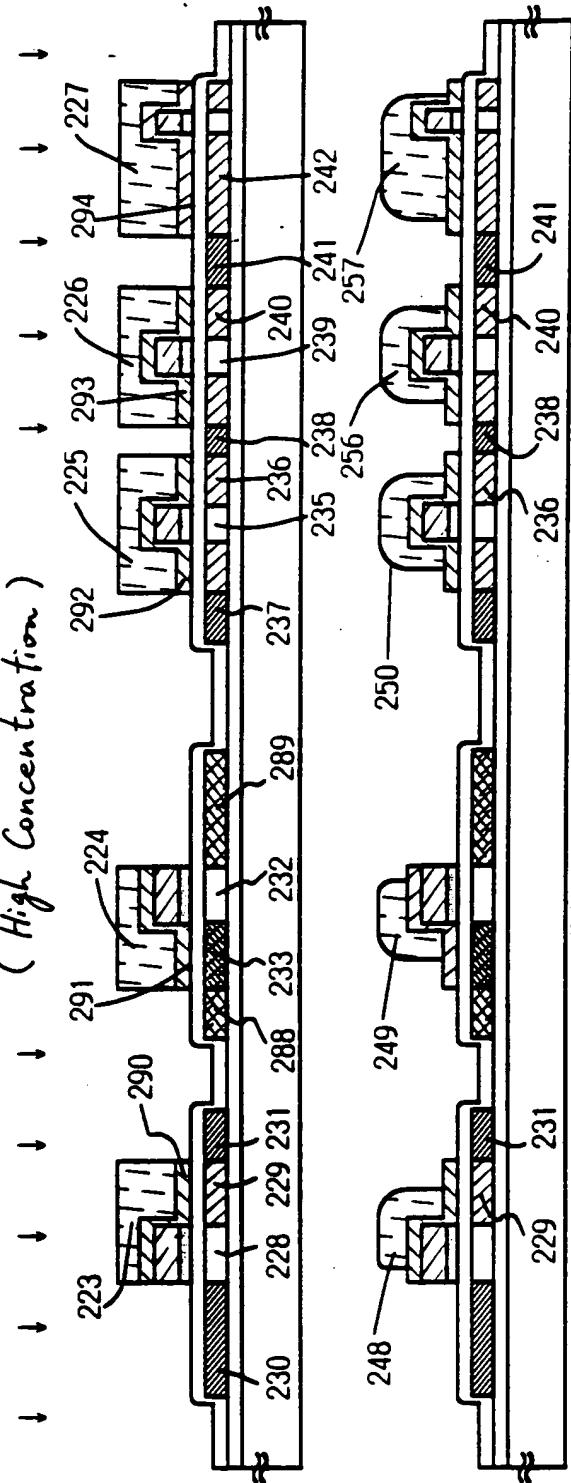


Fig. 6A

Fig. 6B

Fig. 6C

N-Channel TFT P-Channel TFT

CMOS Circuit

Pixel Matrix Circuit

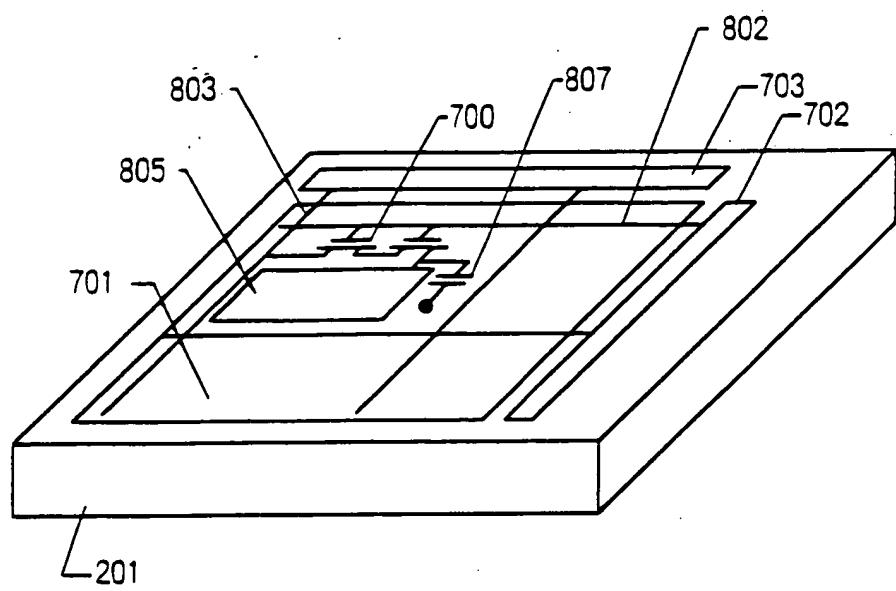


Fig. 7

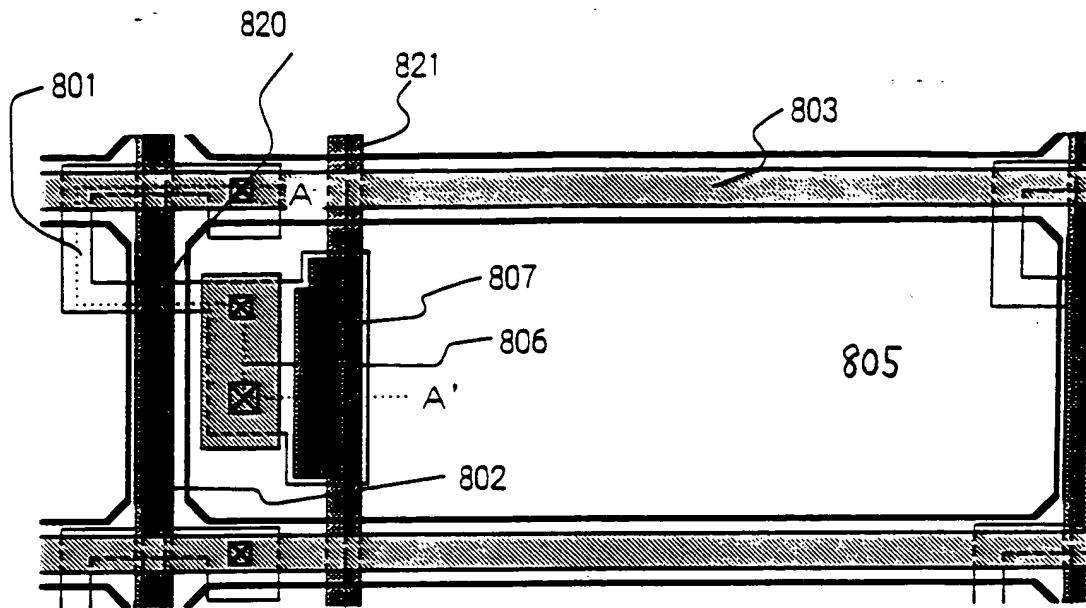


Fig. 8A

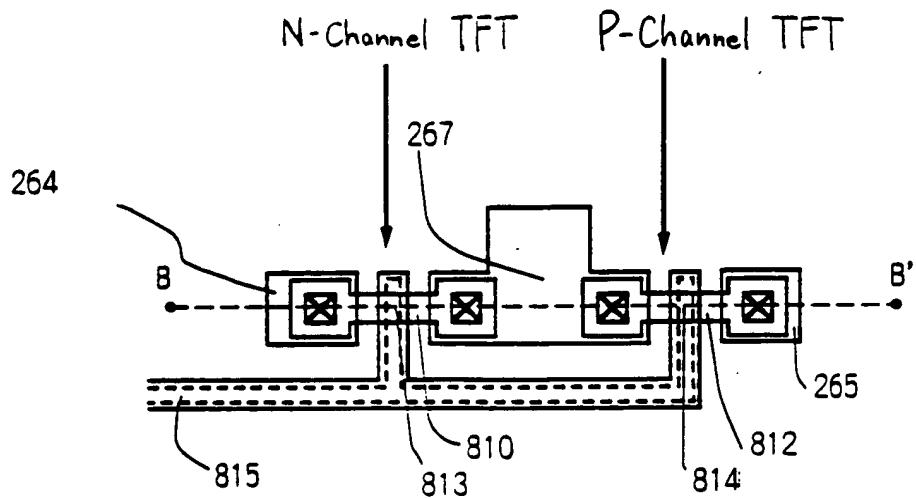


Fig. 8B

Fig. 9A

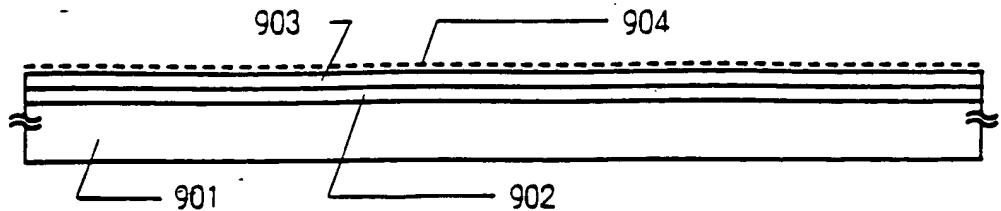


Fig. 9B

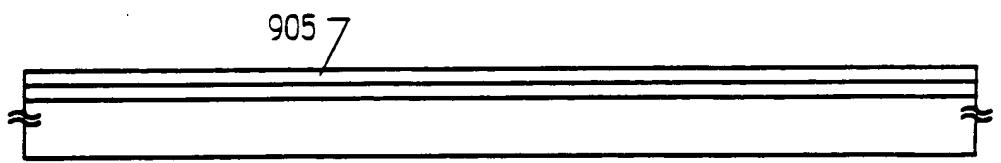


Fig. 10A

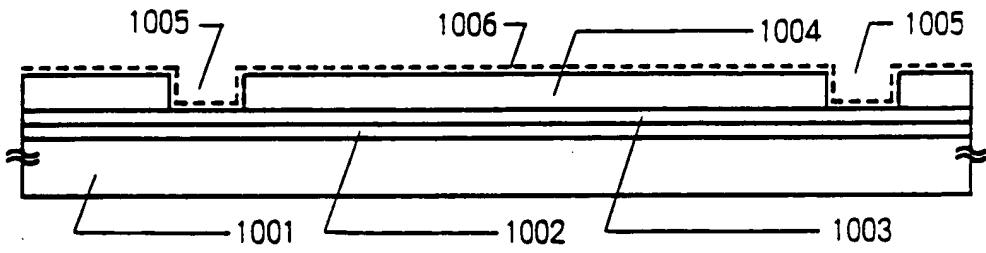
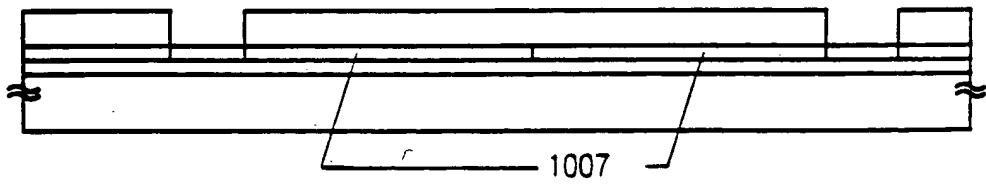
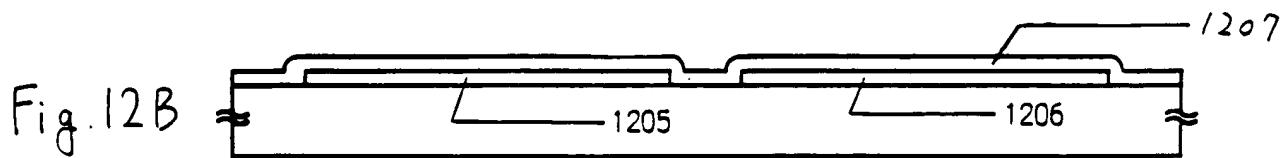
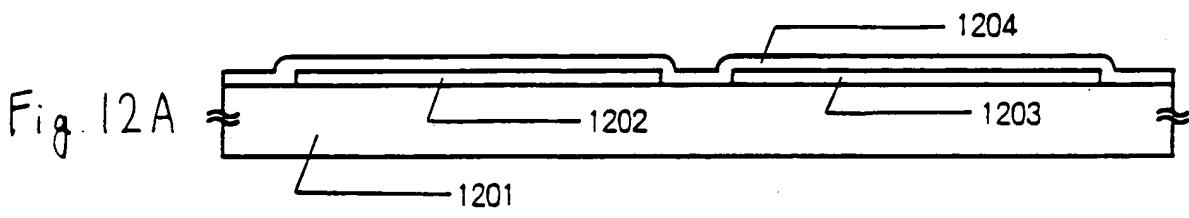
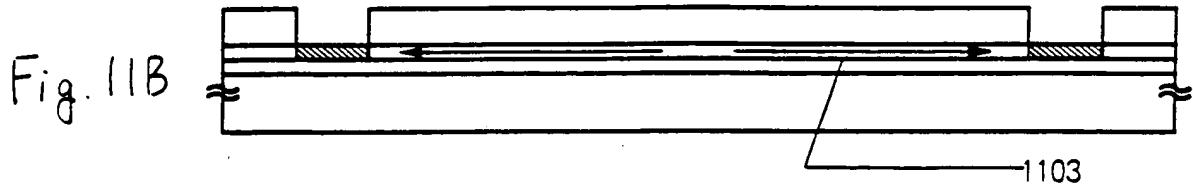
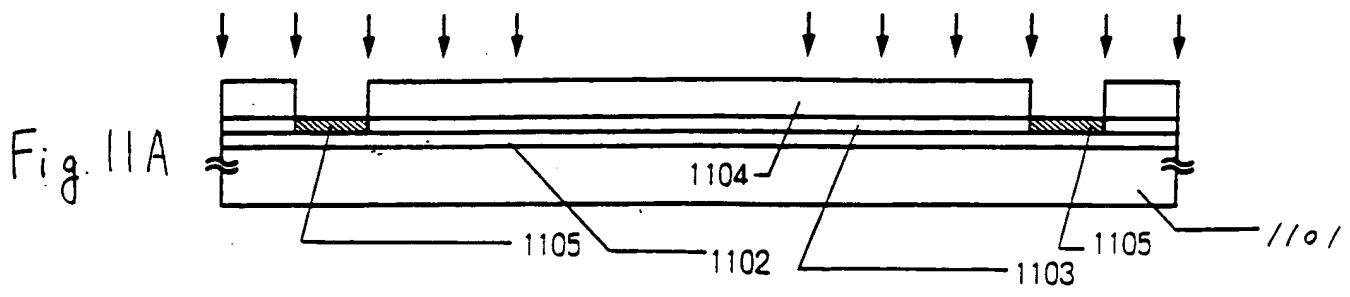


Fig. 10B





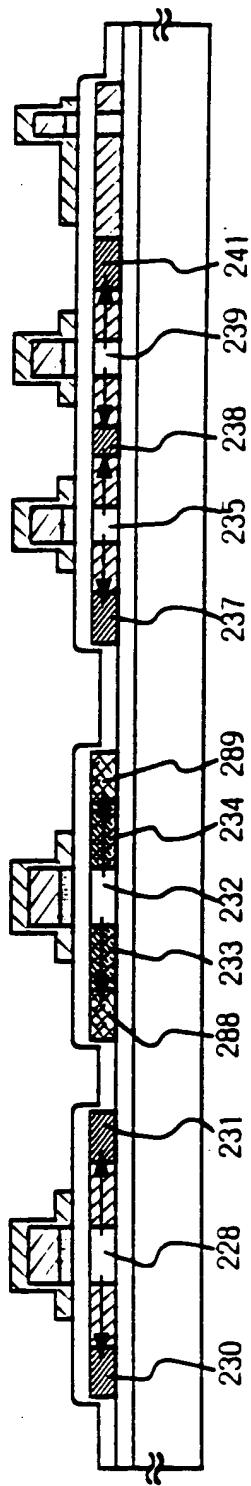


Fig. 13

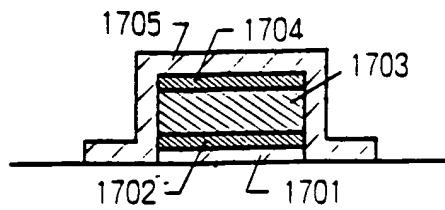


Fig. 14A

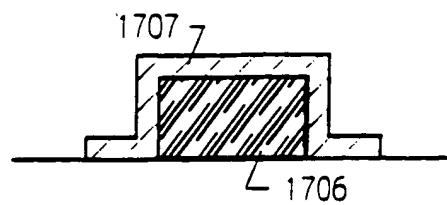


Fig. 14B

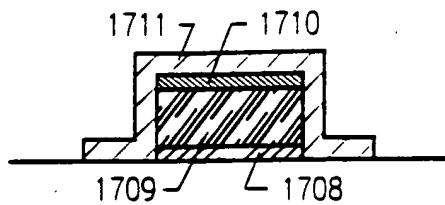


Fig. 14C

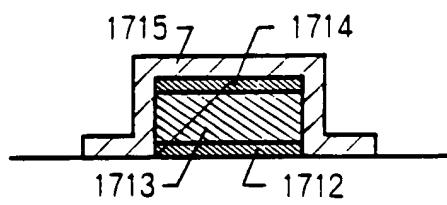


Fig. 14D

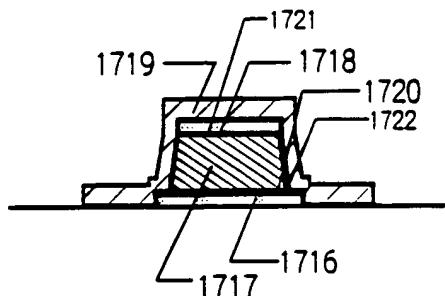


Fig. 14E

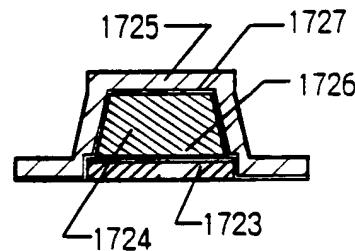


Fig. 14F

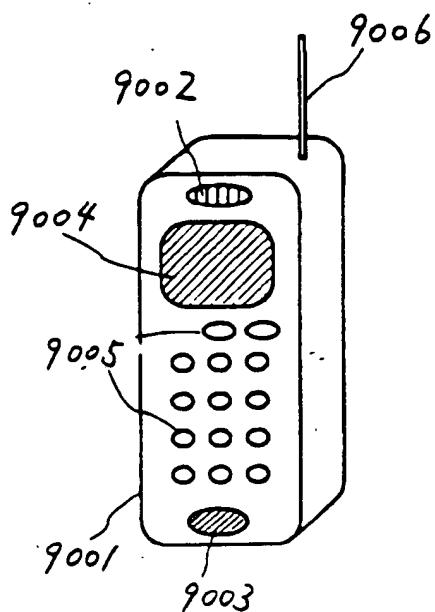


FIG. 15A

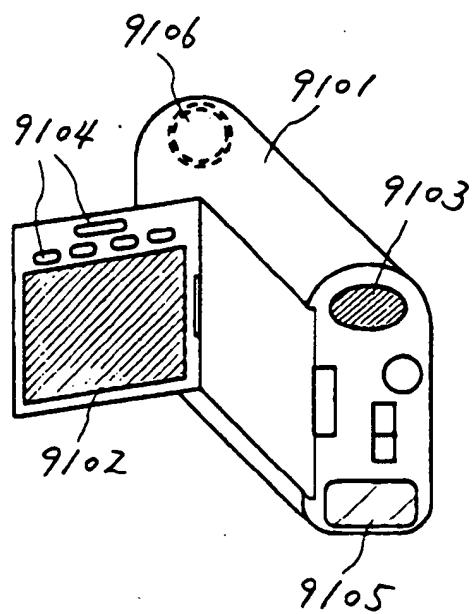


FIG. 15B

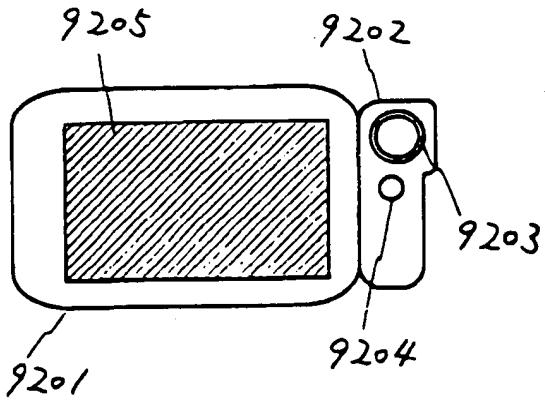


FIG. 15C

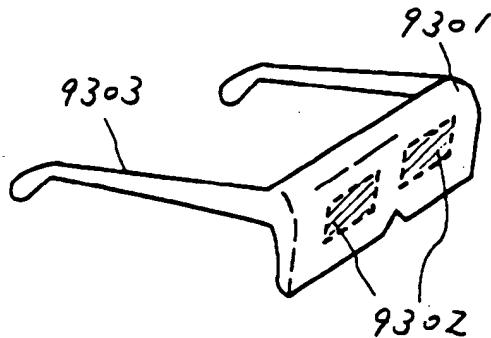


FIG. 15D

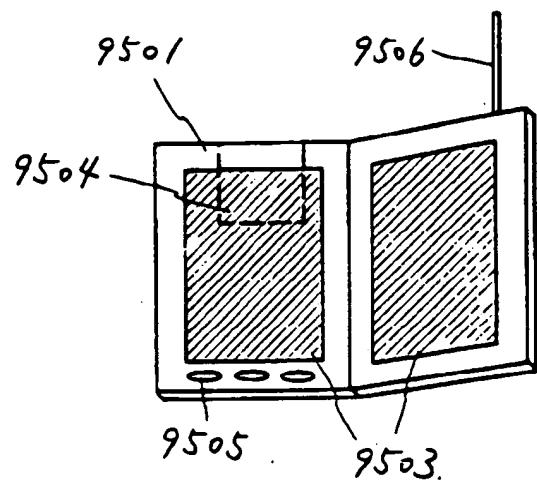


FIG. 15E

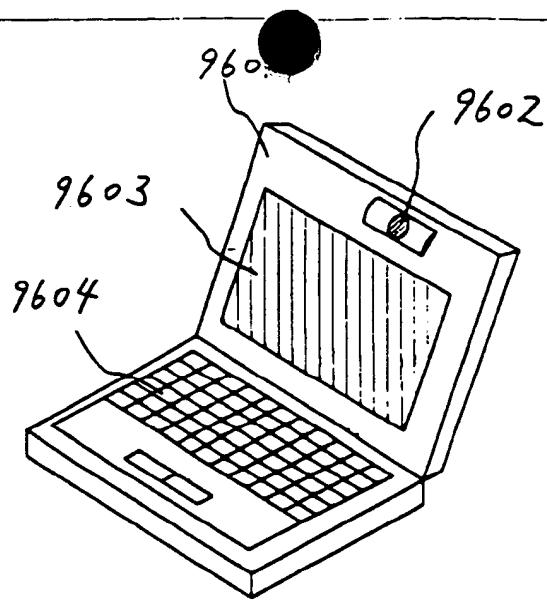


FIG. 15F

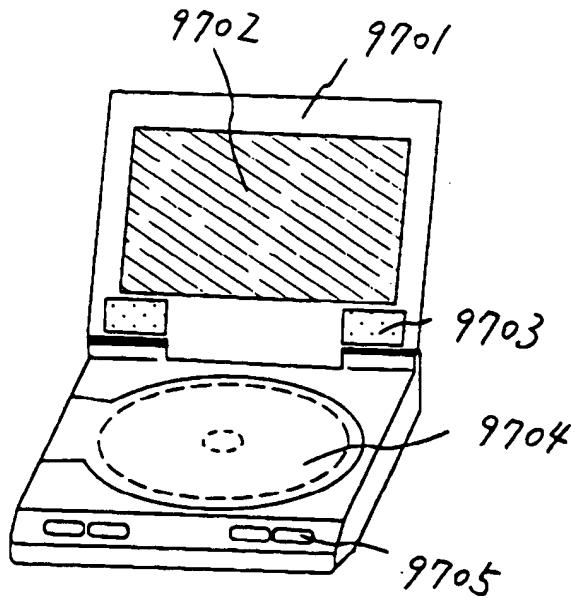


FIG. 15G

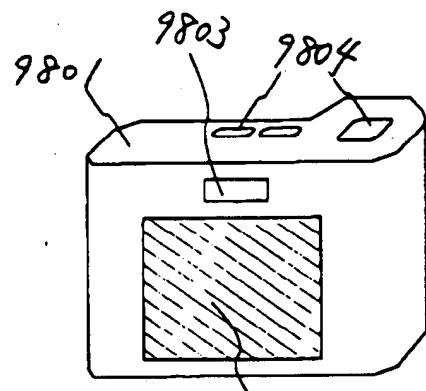


FIG. 15H

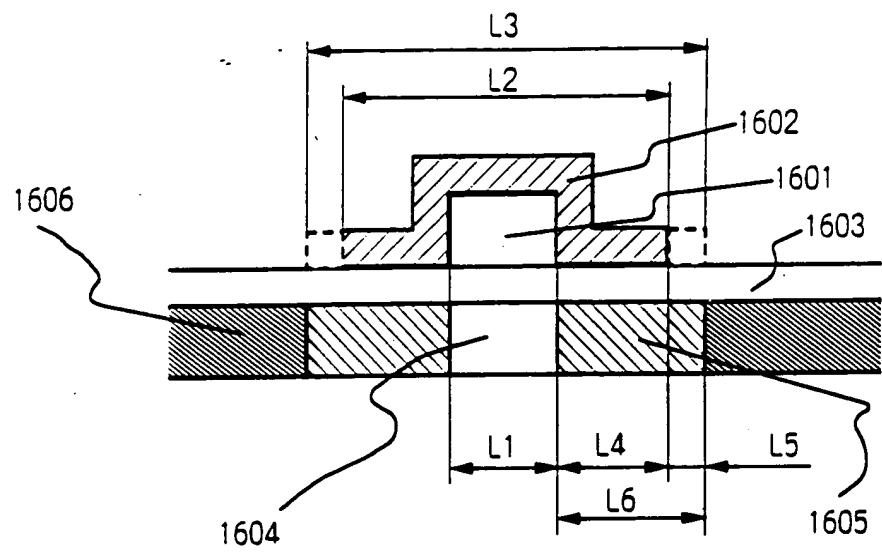
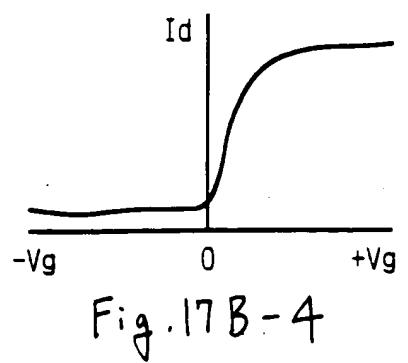
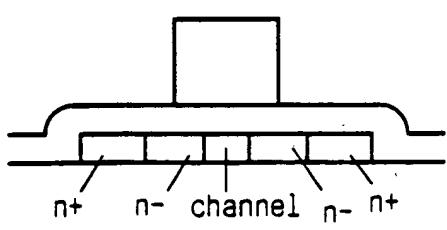
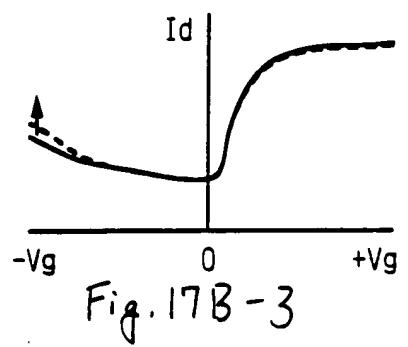
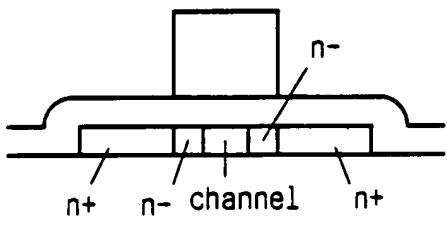
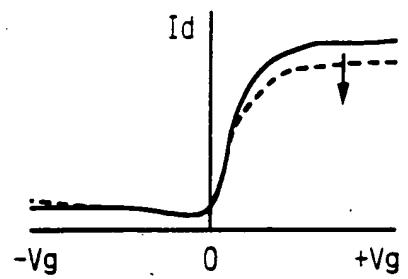
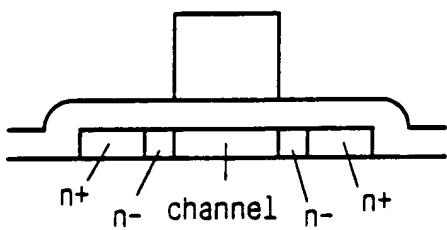
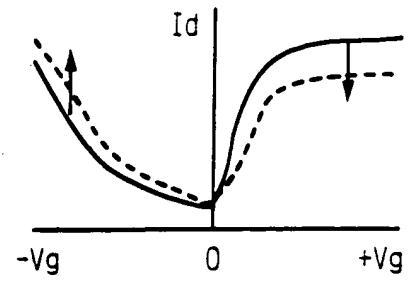
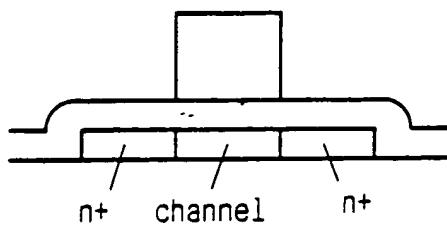


Fig. 16

Fig. 17A-1 to 17A-4
Fig. 17B-1 to 17B-4



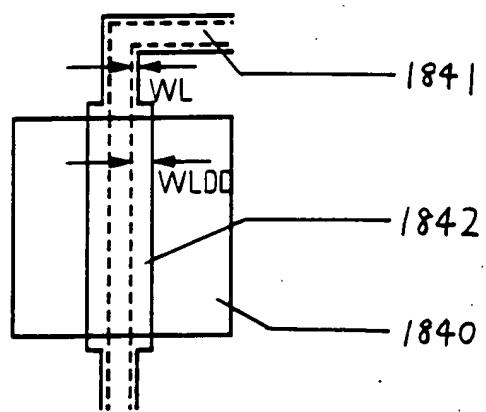


Fig. 18

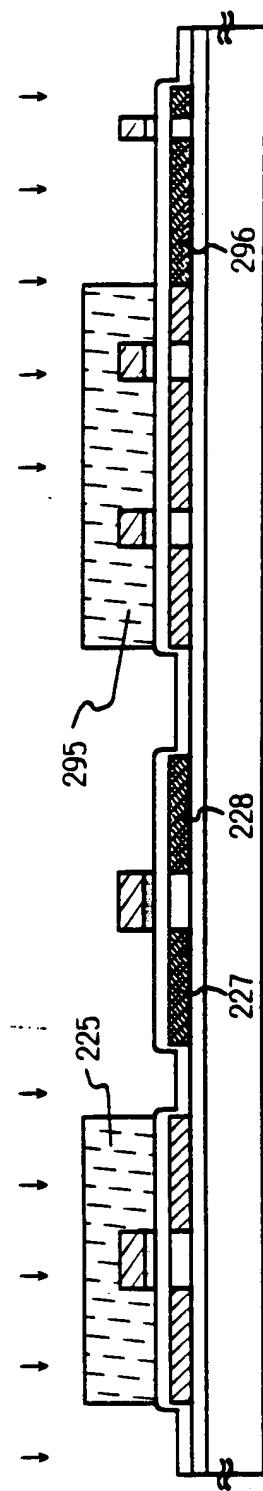
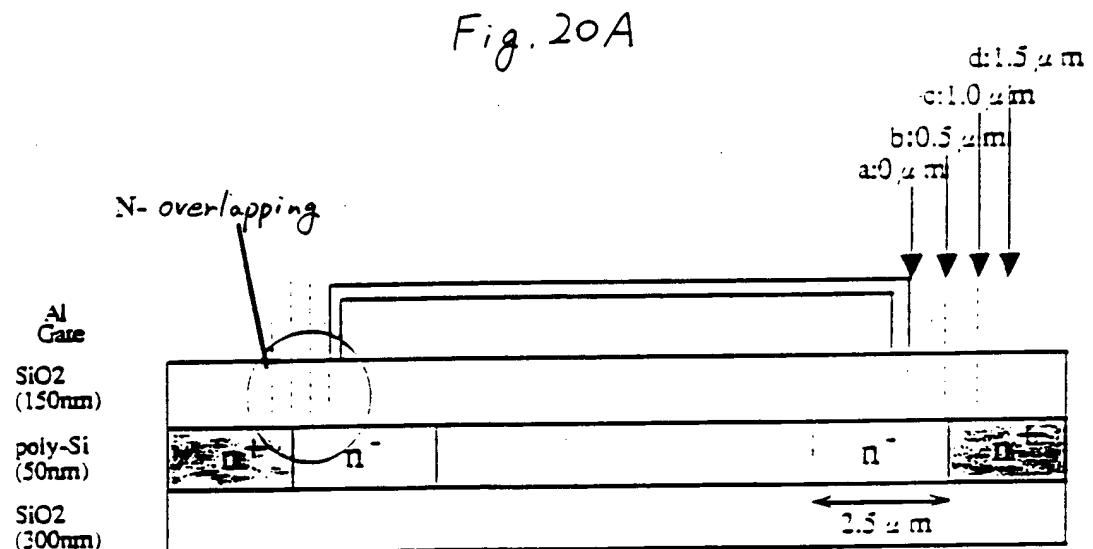
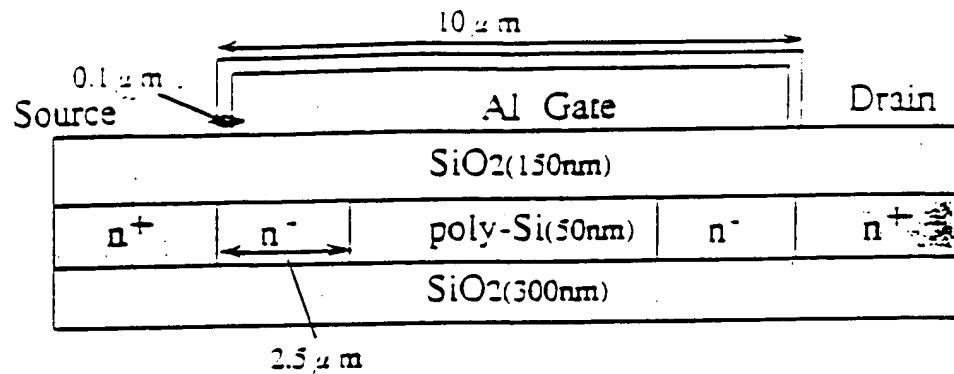


Fig. 19

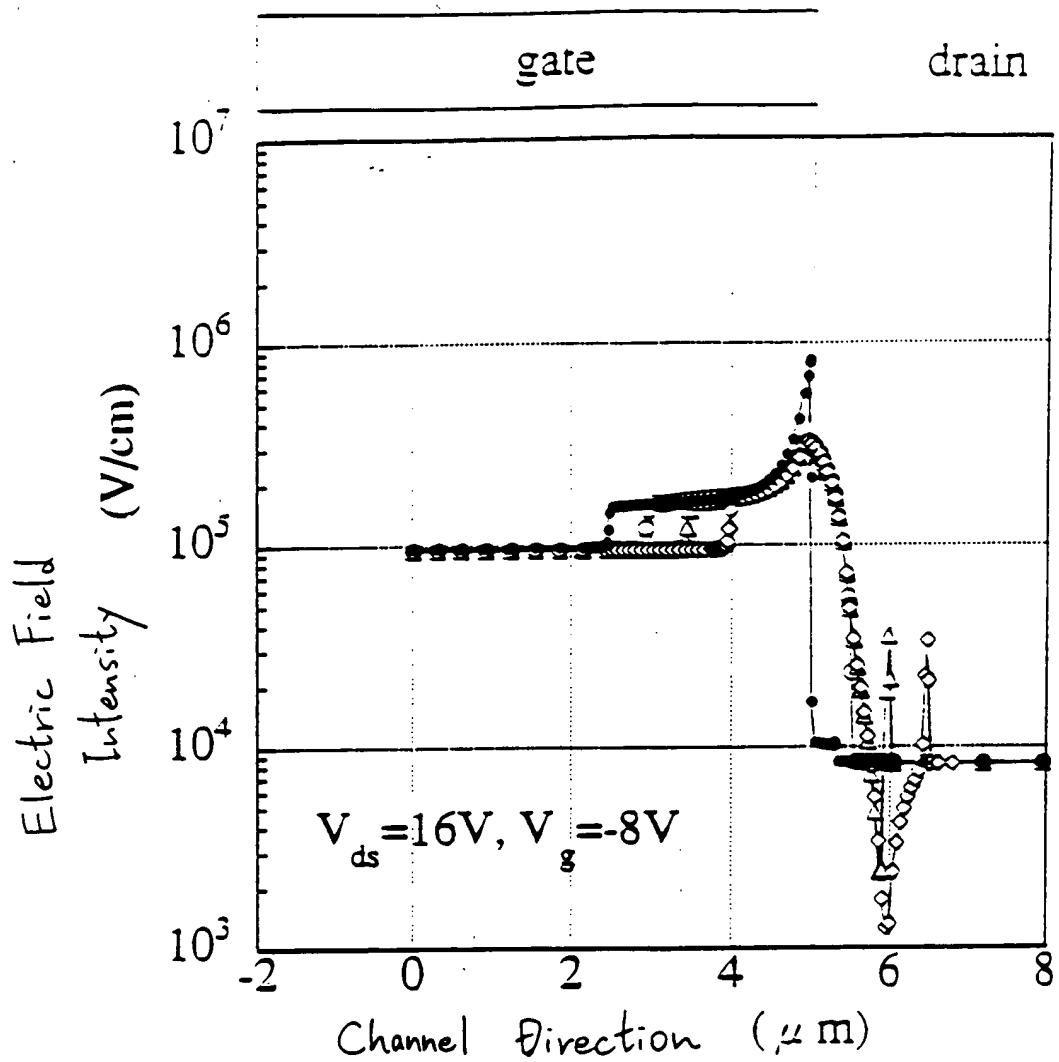


* Width of n⁻ region is fixed
in 2.5 μ m.

Concentration of n⁻ region (activated conc.): 4.2E17/cm³

Concentration of n⁺ region (activated conc.): 2E20/cm³

Fig. 20B



n concentration: $4.2E17/cm^3$

- b: LDD $0.5 \mu m$ + GOLD $2.0 \mu m$
- c: LDD $1.0 \mu m$ + GOLD $1.5 \mu m$
- d: LDD $1.5 \mu m$ + GOLD $1.0 \mu m$
- a: LDD $0 \mu m$ + GOLD $2.5 \mu m$

Fig. 21

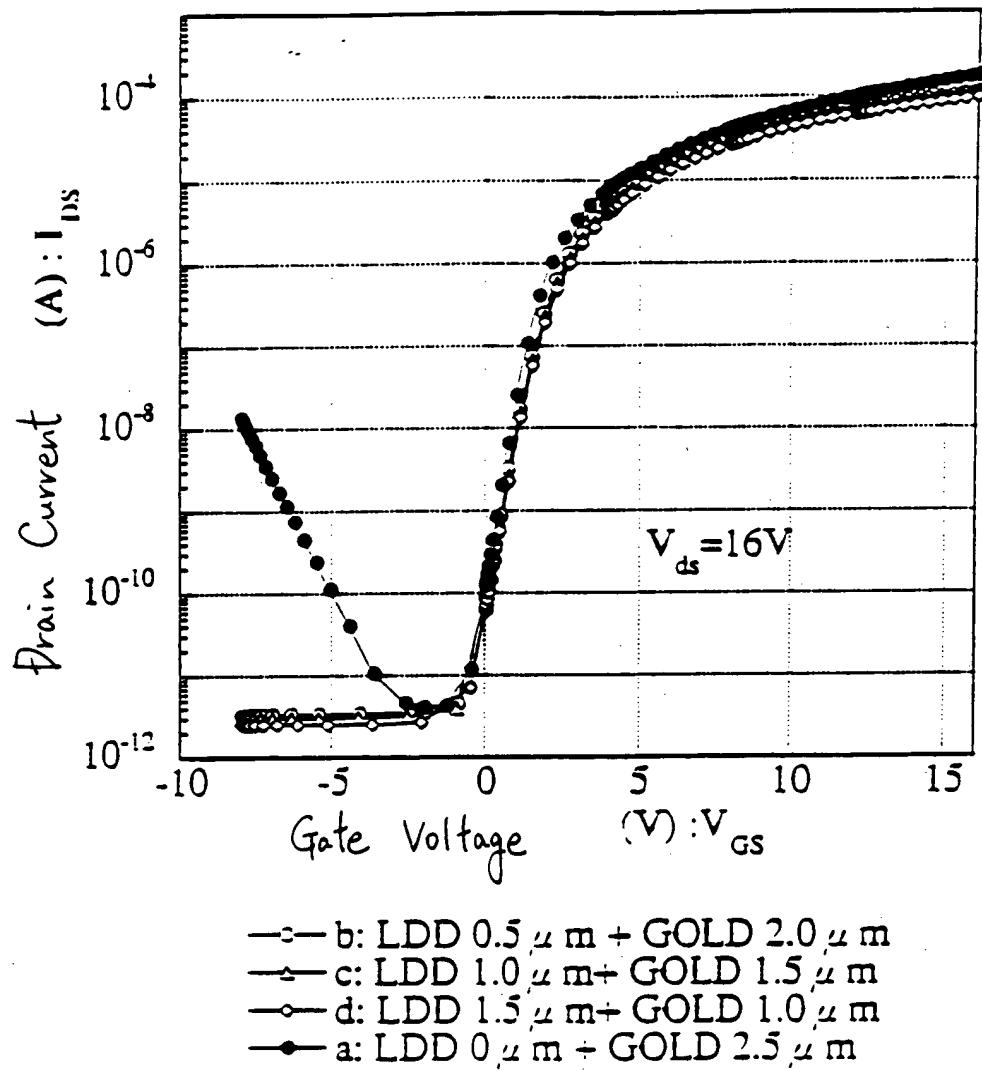


Fig. 22

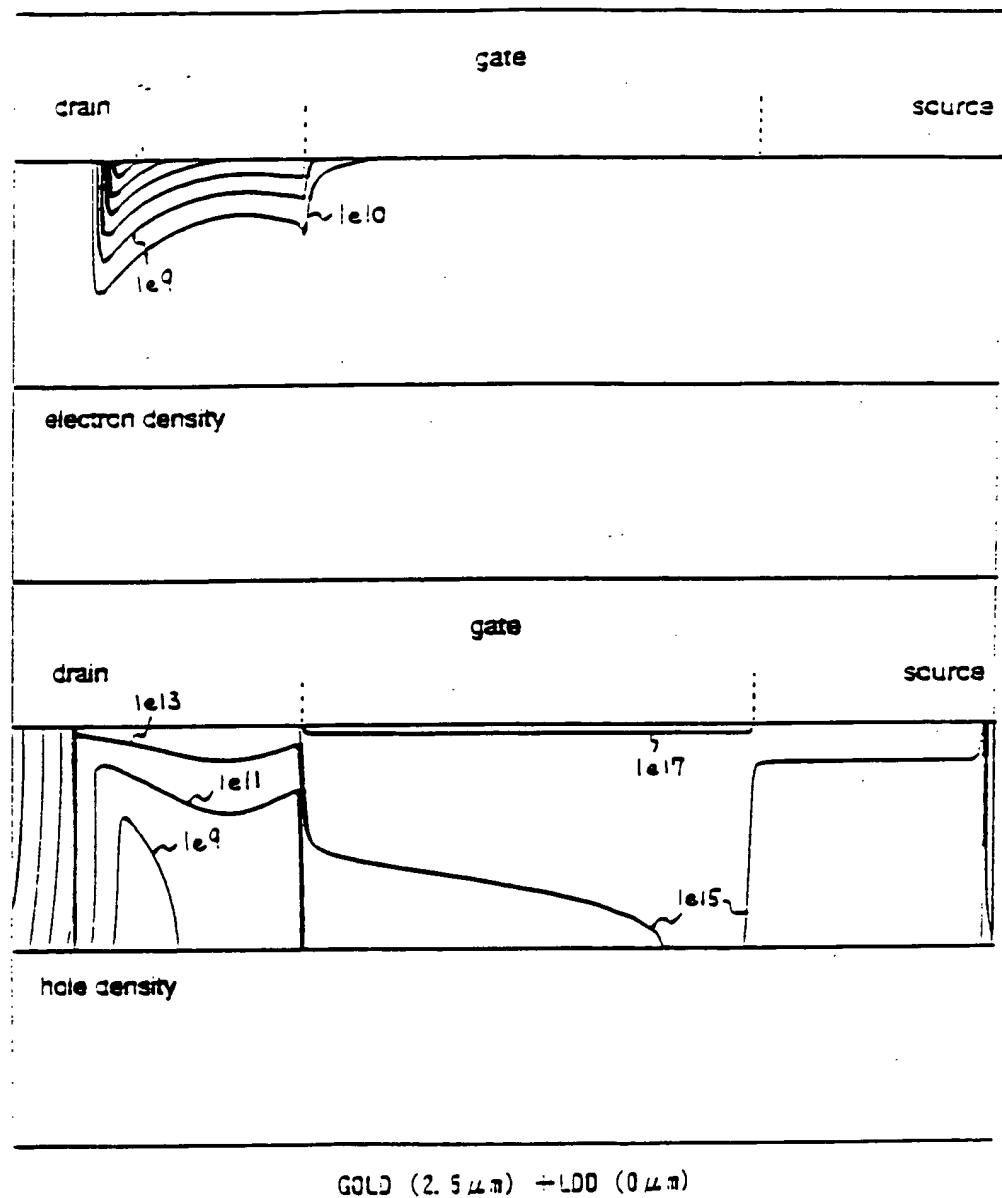
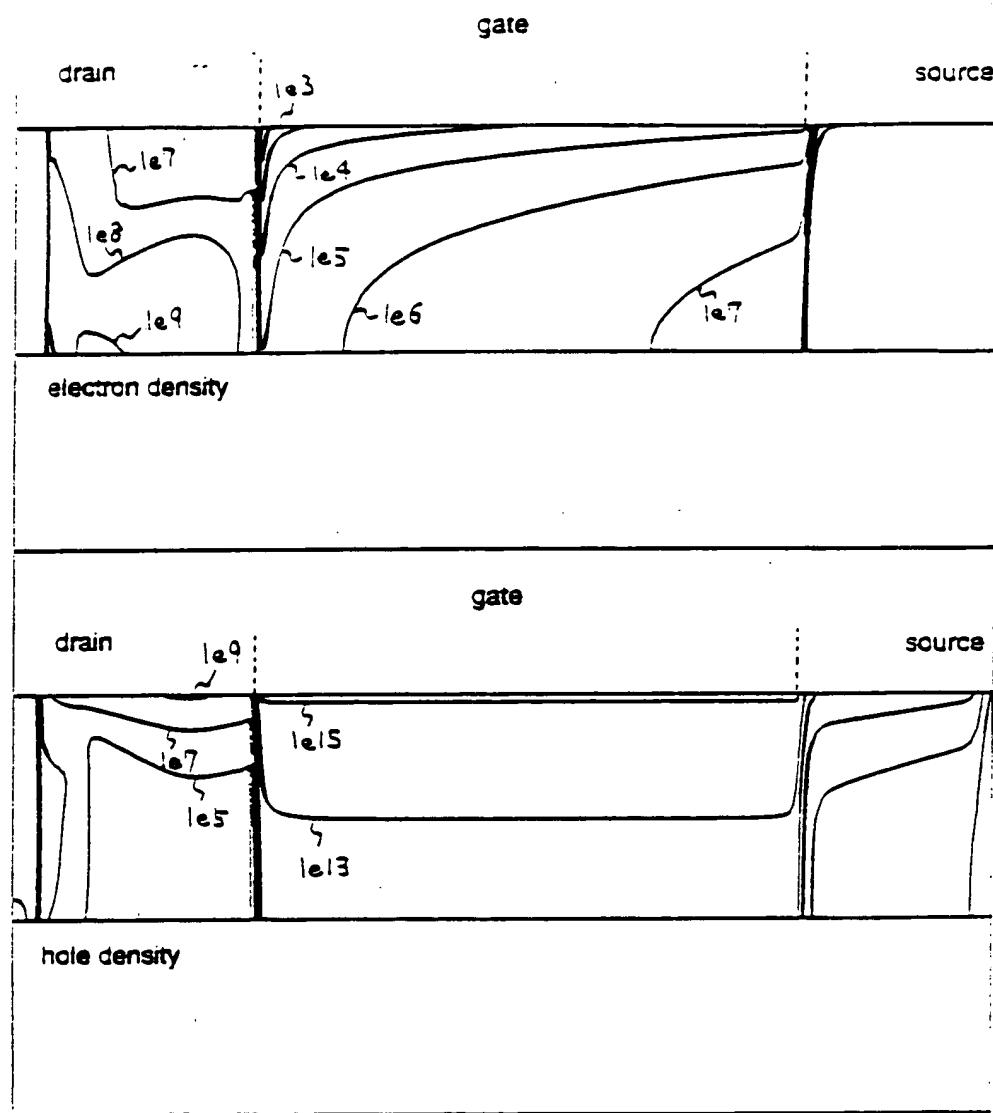
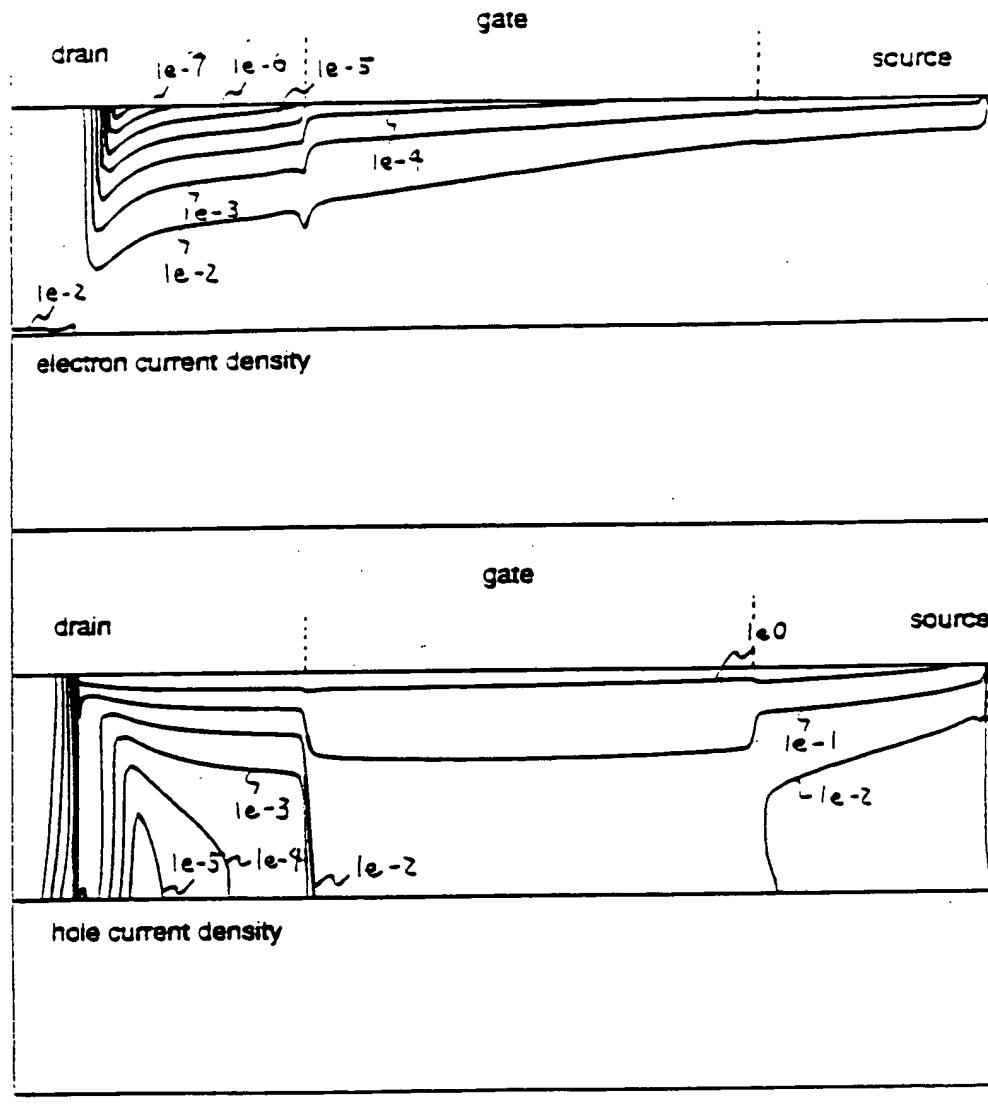


Fig. 23



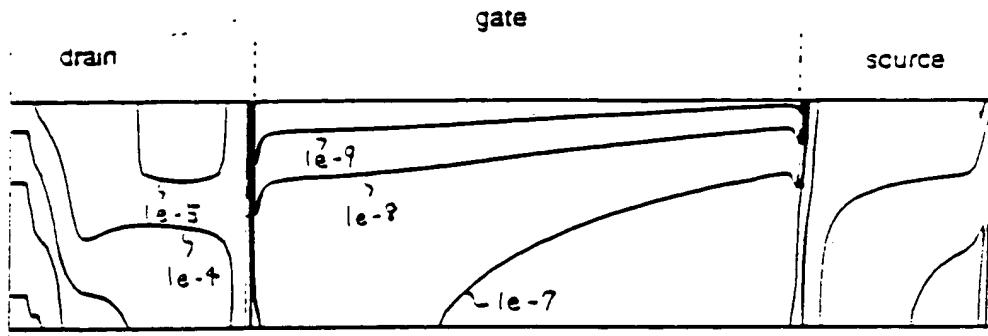
GOLD ($2.0 \mu\text{m}$) + LDD ($0.5 \mu\text{m}$)

Fig. 24

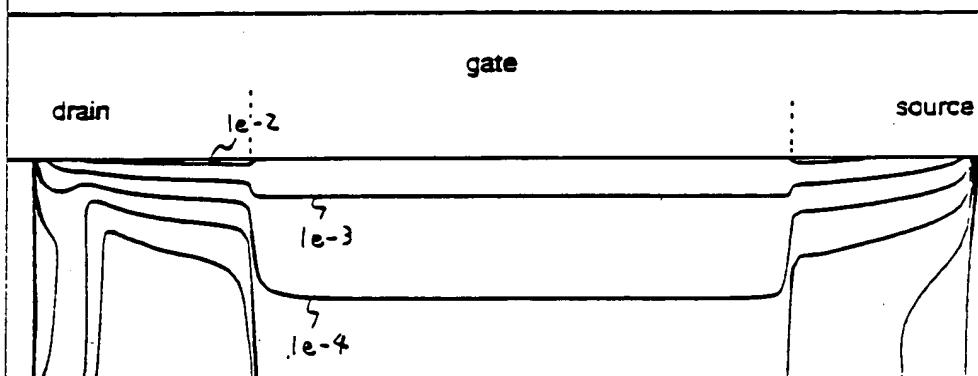


GOLD ($2.5 \mu m$) \rightarrow LDD ($0 \mu m$)

Fig. 25



electron current density



hole current density

GOLD ($2.0 \mu m$) + LDD ($0.5 \mu m$)

Fig. 26

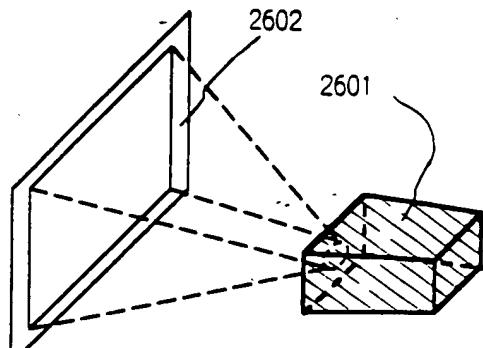


Fig. 27A

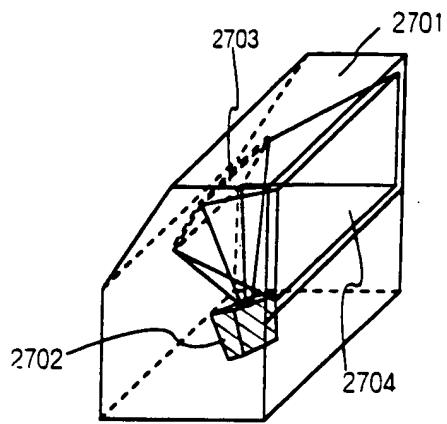


Fig. 27B

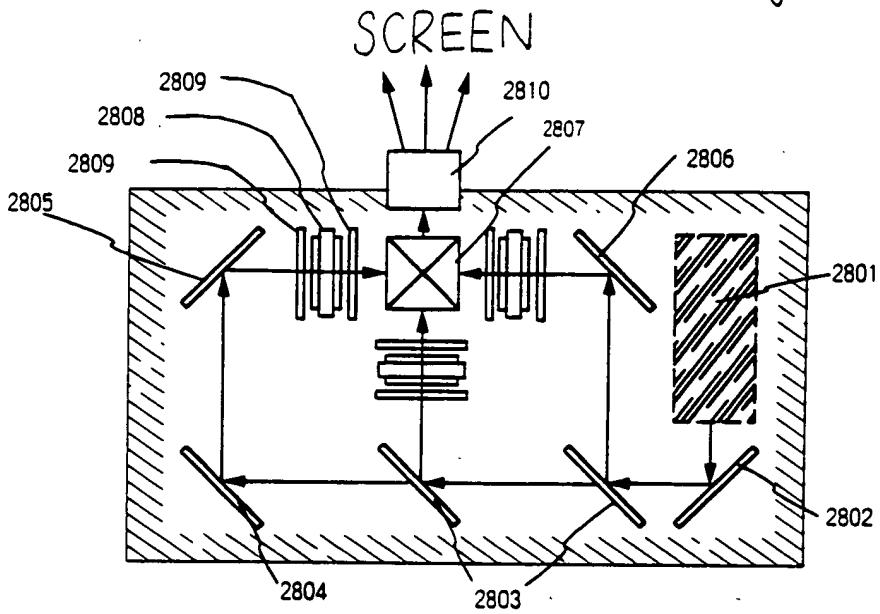


Fig. 27C

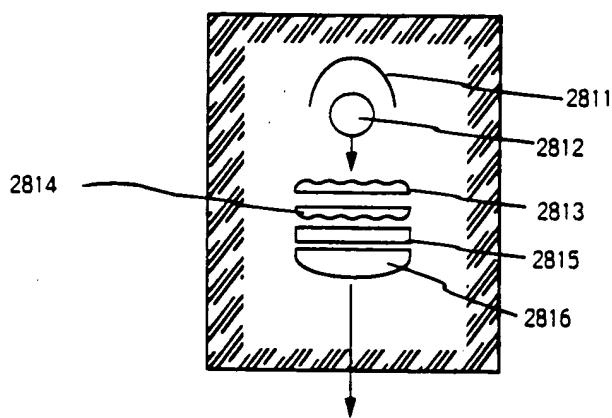


Fig. 27D

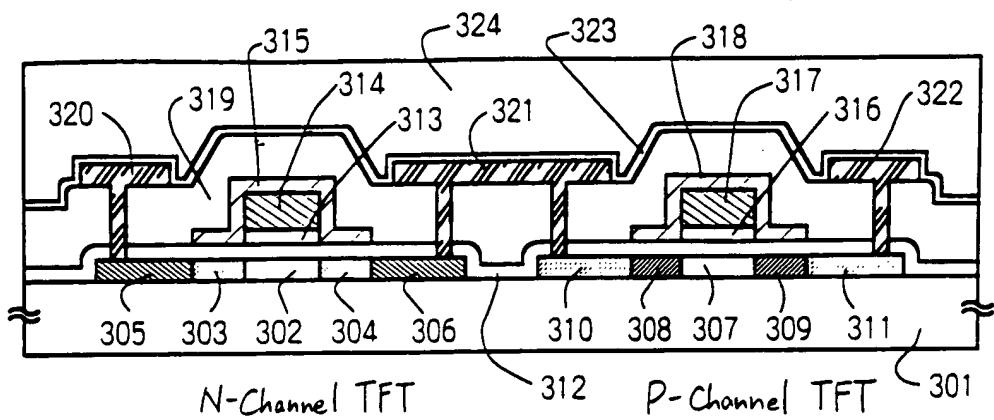


Fig. 28

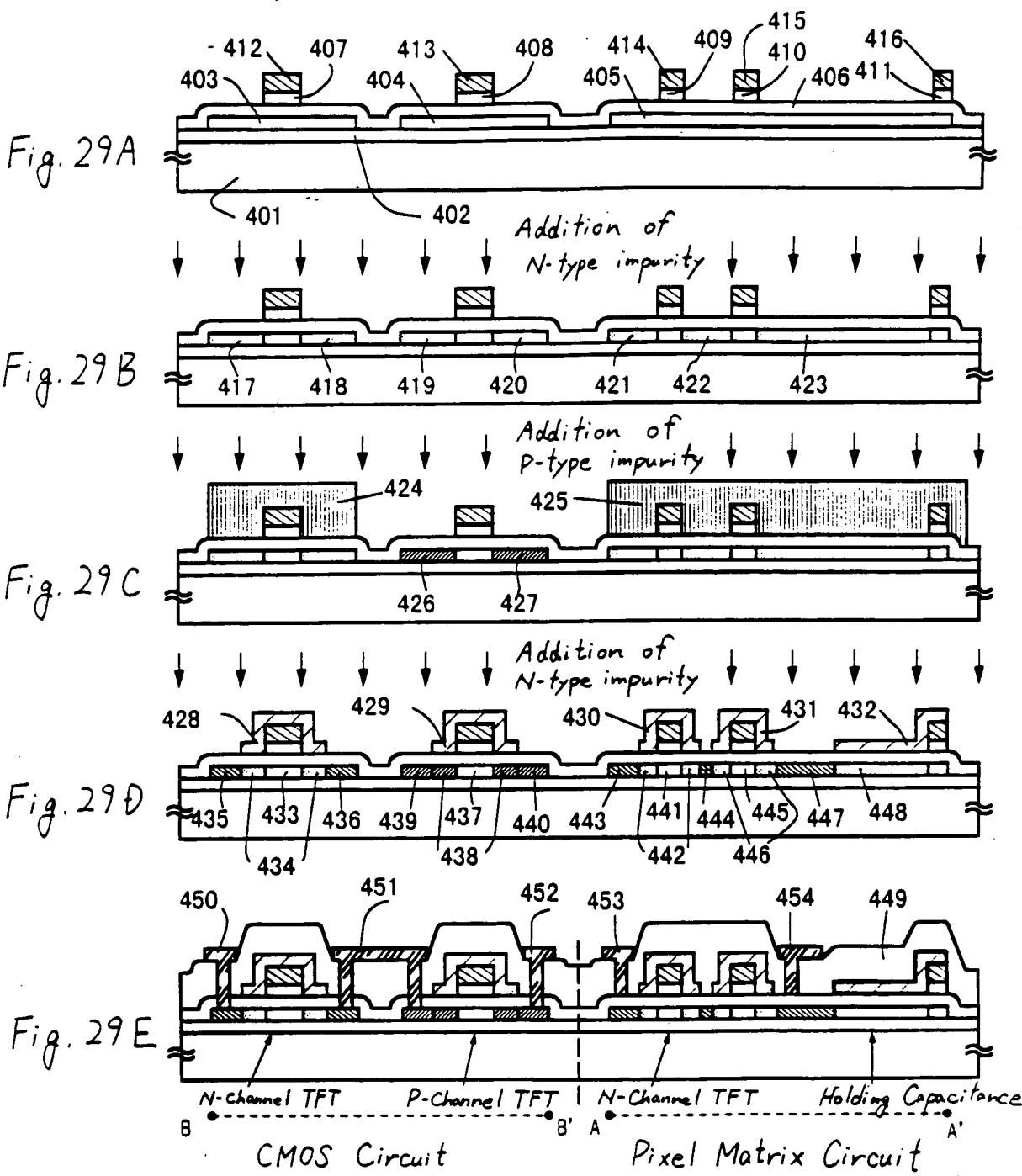


Fig. 30A

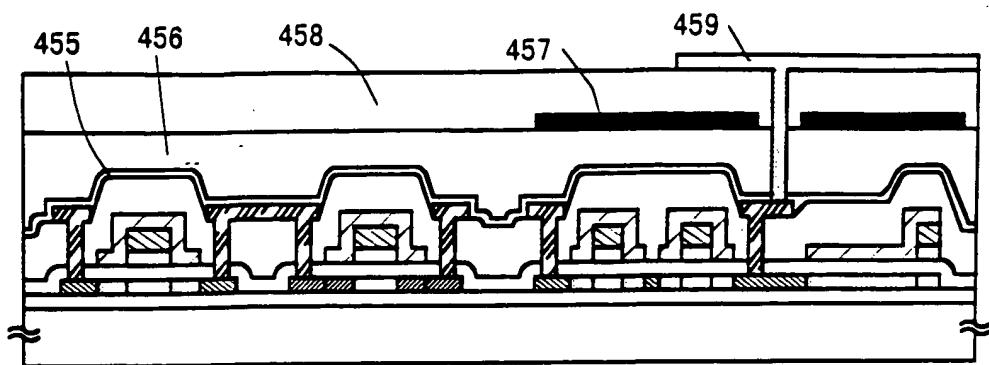
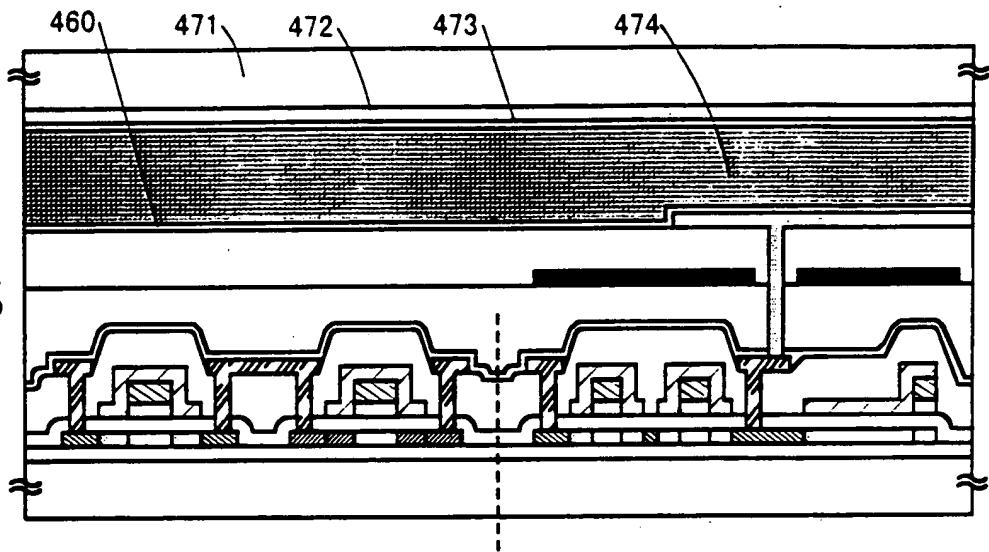


Fig. 30B



3103 : Second Conductive Layer

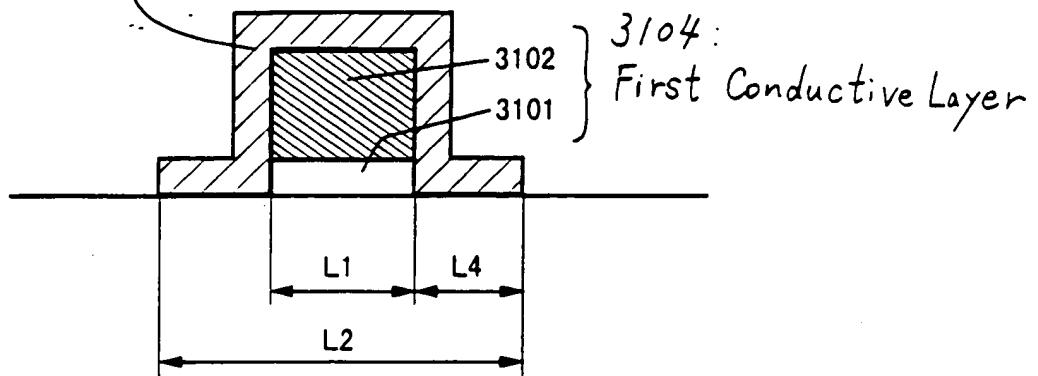


Fig. 31

3201 3202 3203 3204 3205 3206 3207 3208 3209

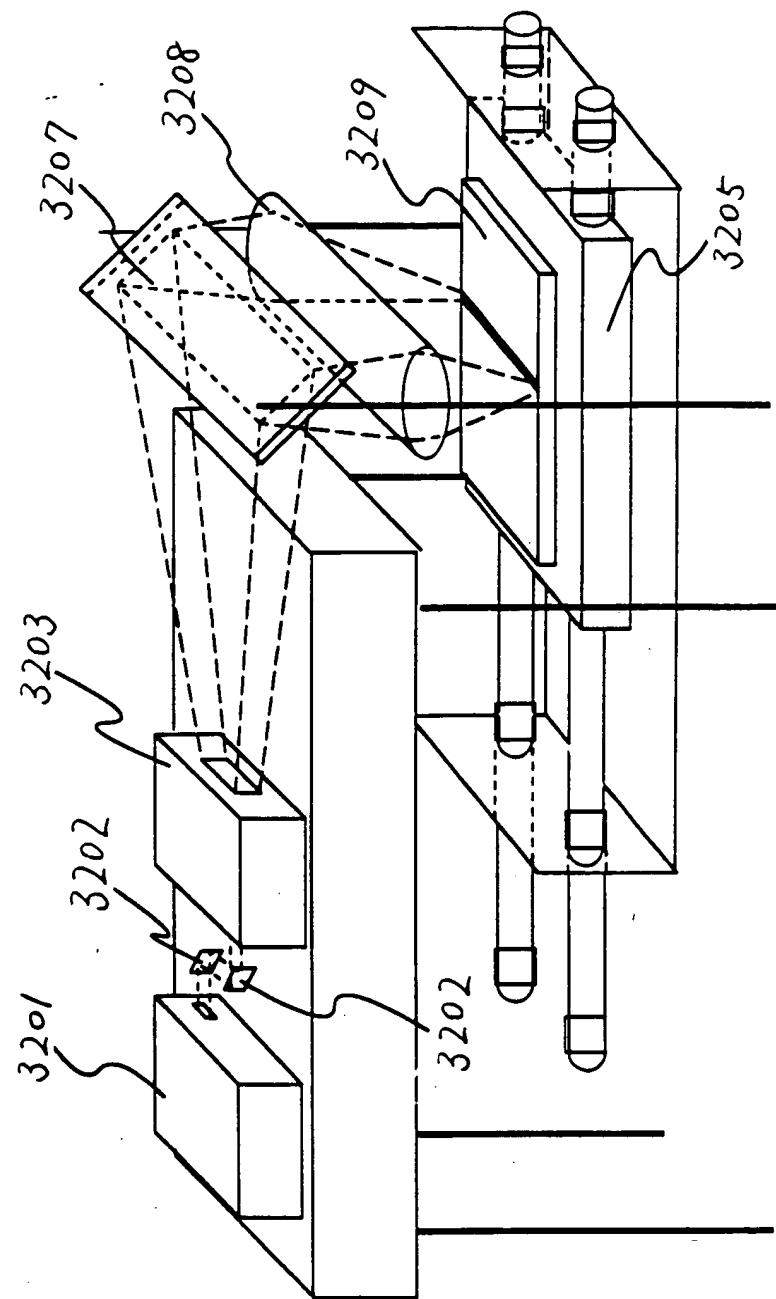


Fig. 32

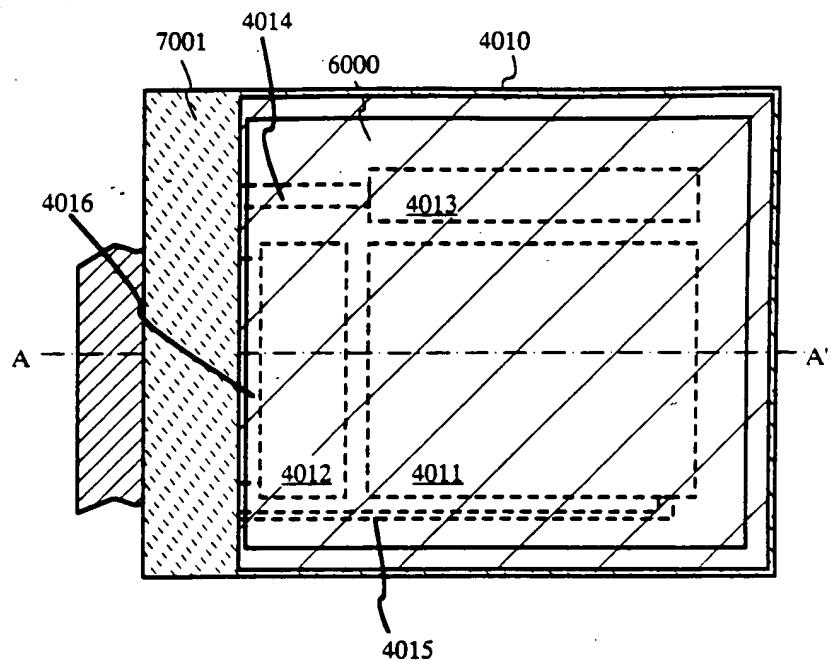


Fig. 33A

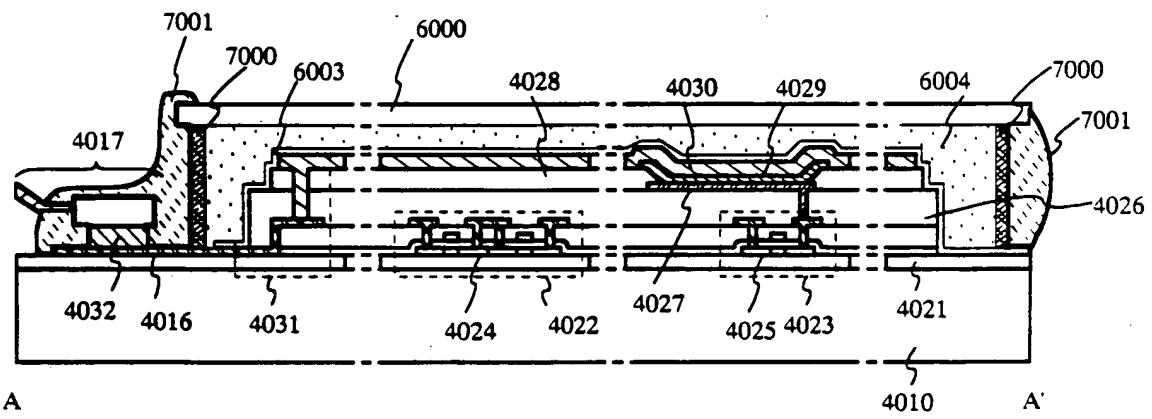


Fig. 33B

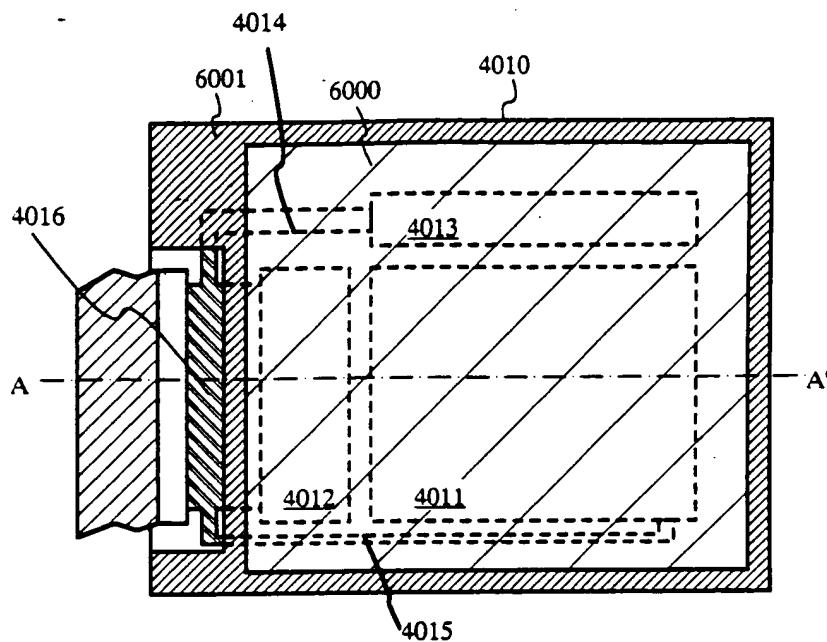


Fig. 34A

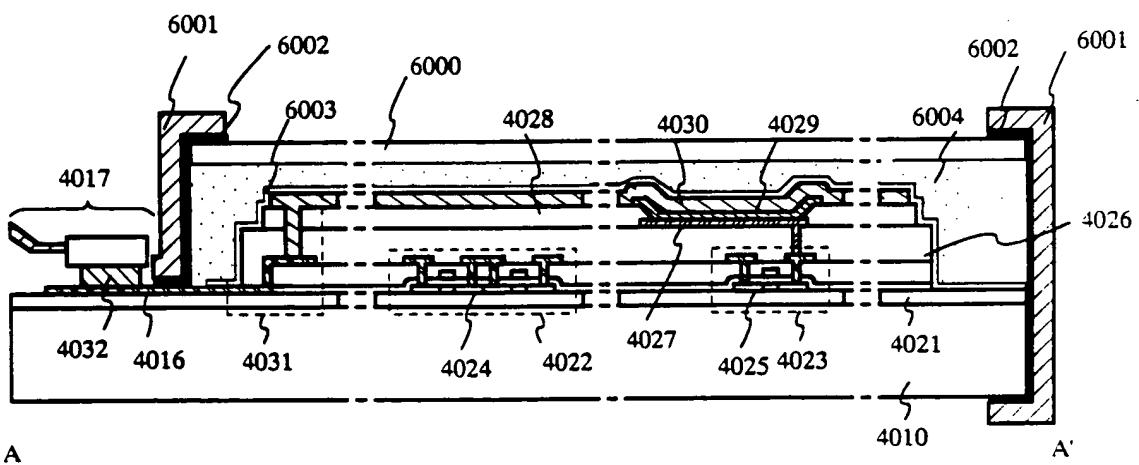


Fig. 34B

FIG. 35. A cross-sectional view of a liquid crystal display cell showing the structure of the EL element and the TFTs.

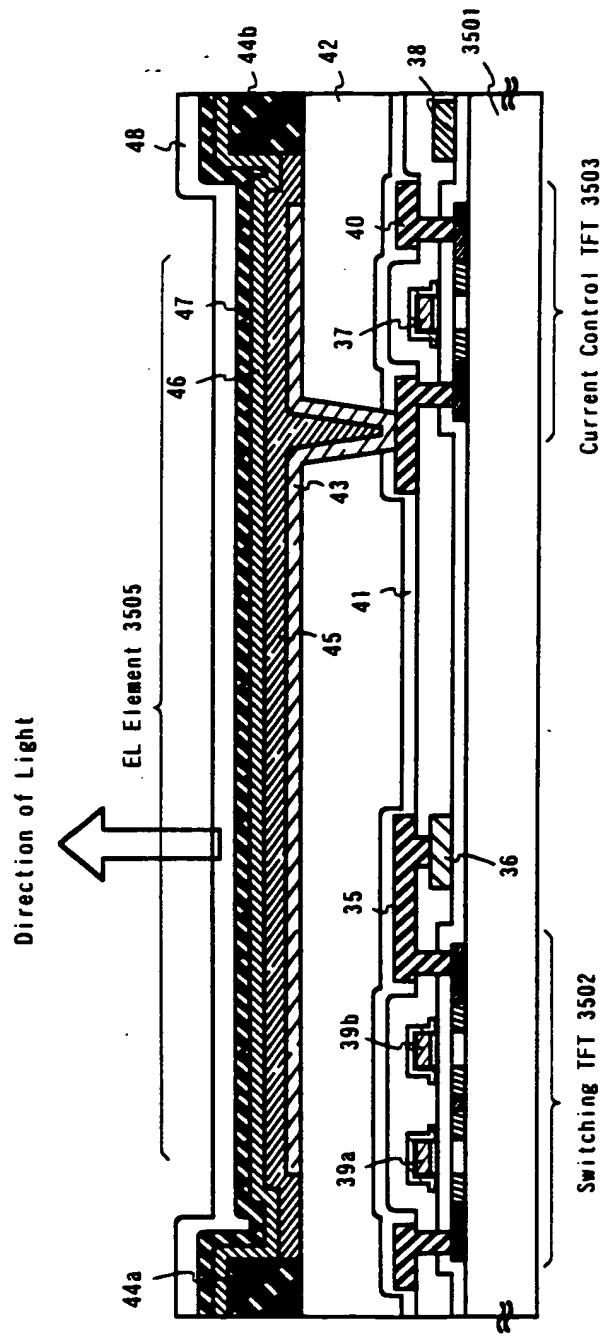


Fig. 35

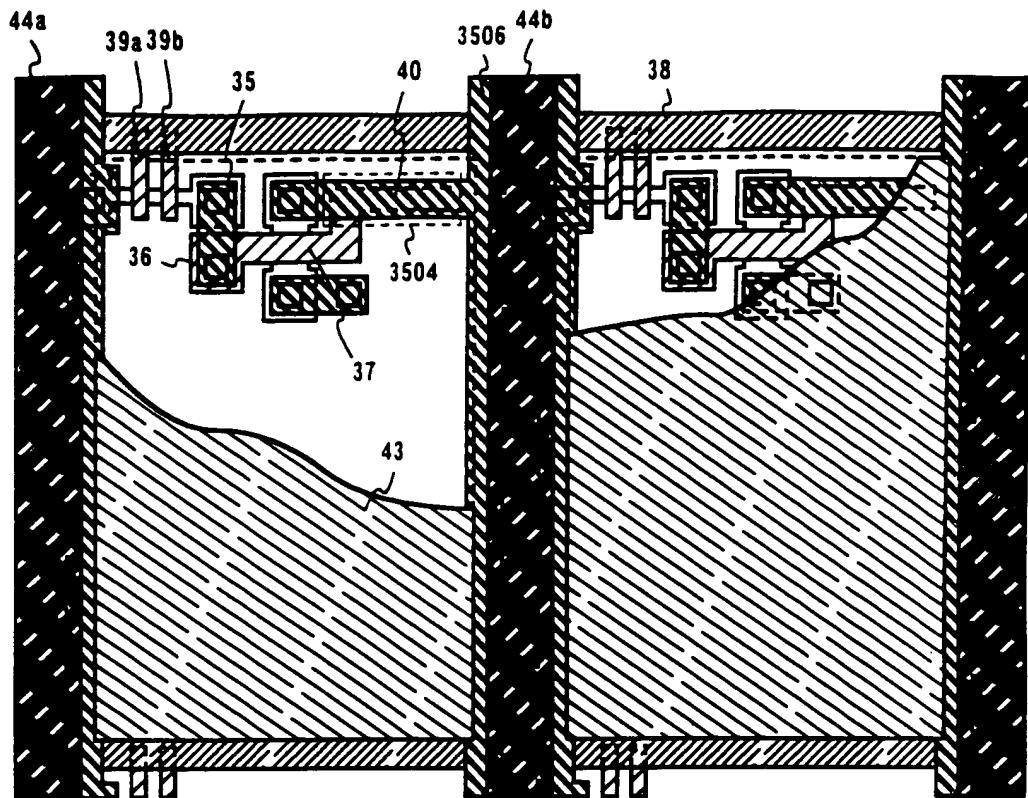


Fig. 36A

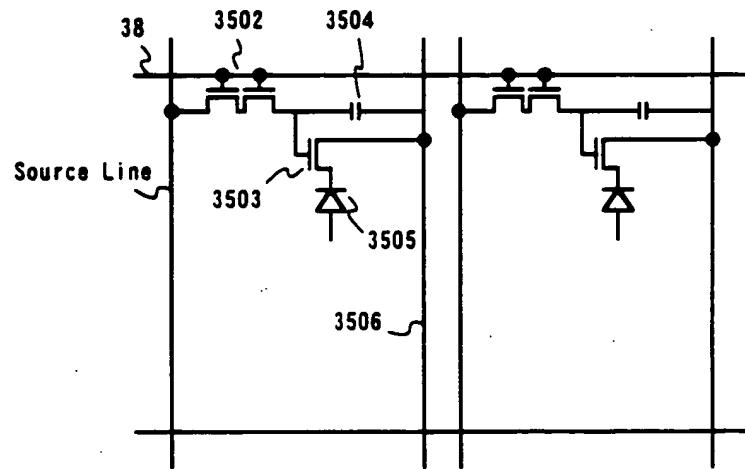


Fig. 36B

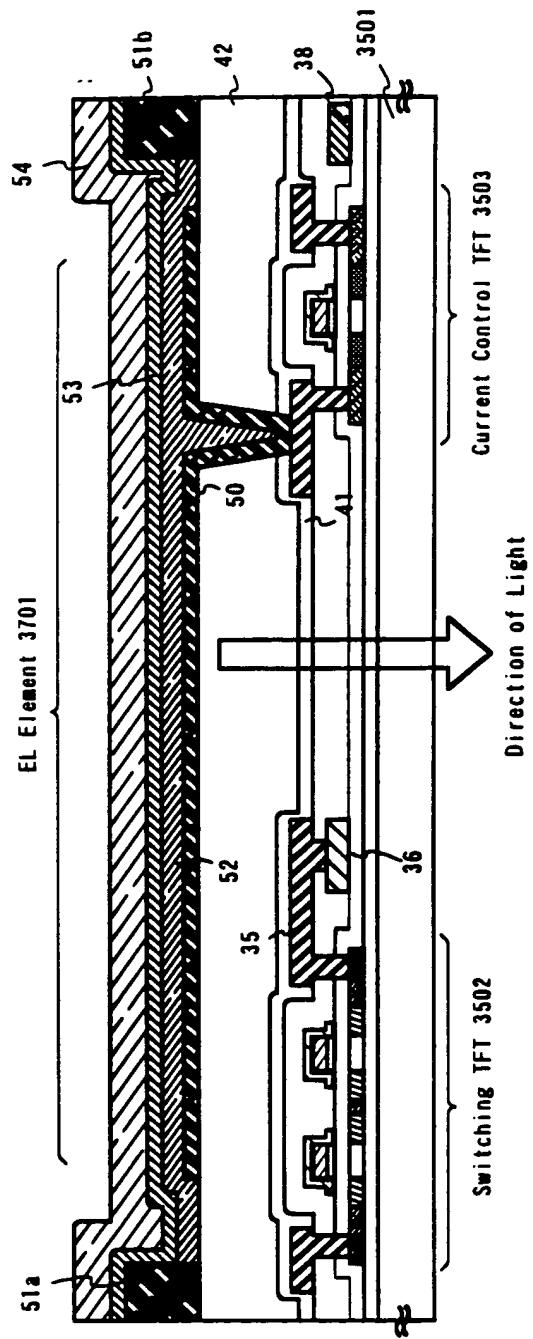


Fig. 37

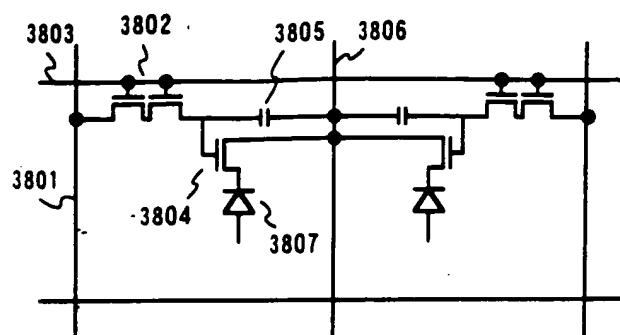


Fig. 38A

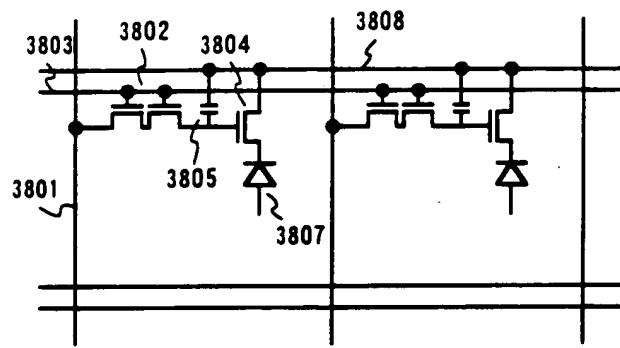


Fig. 38B

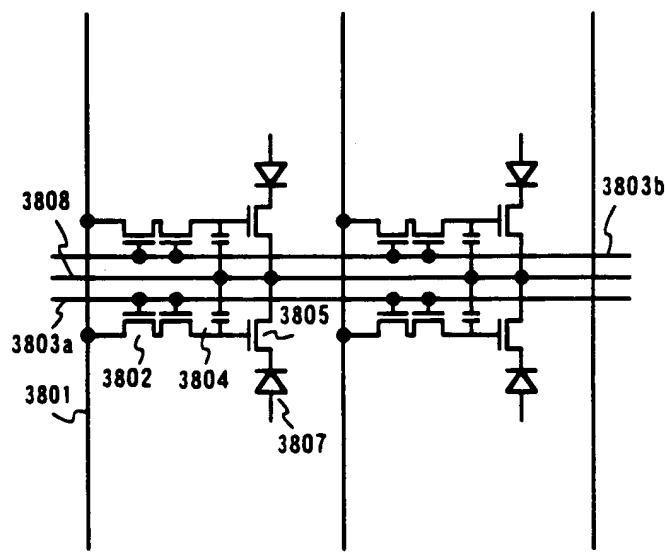


Fig. 38C

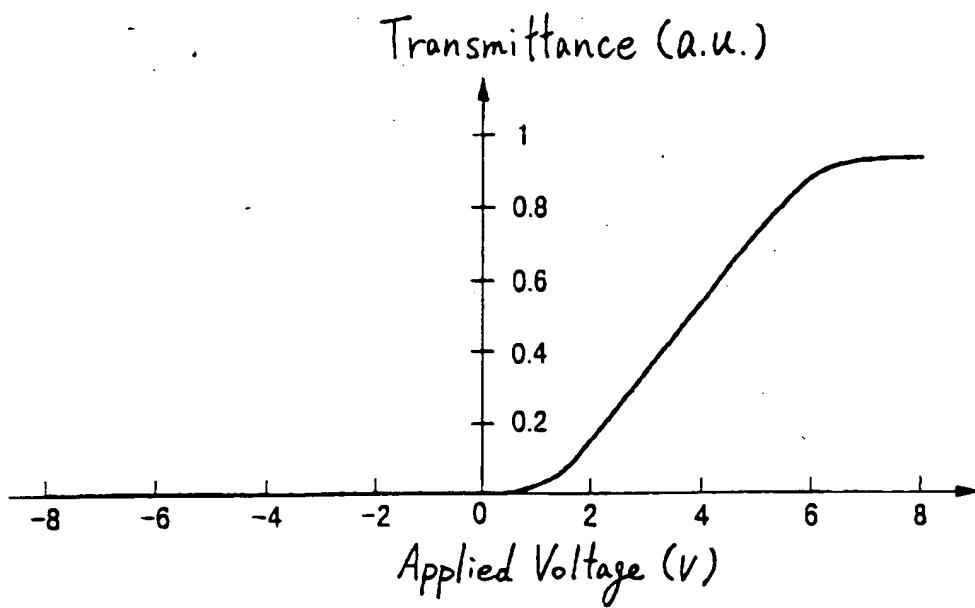


Fig. 39